

Abstract:

System for flushing at least one internal space of an  
objective

(Figure)

In a system for flushing at least one internal space of an objective, in particular an exposure projection objective for semiconductor lithography, flushing is performed by mixing at least two inert gasses in such a way that the refractive index resulting therefrom corresponds at least approximately to the refractive index of air.

10020551-120701